**Description**

The HMxSquare is designed to address the needs of the semiconductor industry regarding to automation of substrate wet cleaning, photoresist development and chrome wet etching in photomask applications as well as in optoelectronics, OLED, and special semiconductor back-end (MEMS) applications.

HMxSquare offers programmed development, etching and cleaning functionalities. Active liquids are pneumatically transferred to spray nozzles and sprayed on rotating substrates. In the end of process the substrate is washed and centrifugally dried.

**Specifications / Capabilities**

- Wet cleaning processes: Acid cleaning (Piranha), 1 MHz megasonic cleaning by DI Ammonia
- Development process: with developer 400K
- Etching process: Chrome etchant

Substrate sizes: 2 inch to 5 inch

**Link**